

## IN THE CLAIMS

Per the revised amendment practice, a complete listing of all claims in the application follows.

Claims 1-36 (Canceled).

37. (Currently amended) An atmosphere for a chemical vapor deposition process, comprising:  
a deposition gas having a ~~pressure contribution and a~~ chemical reactivity; and  
a chemically inert reactability increaser gas mixed with said deposition gas, ~~limiting said~~  
~~pressure contribution of said deposition gas, and increasing said chemical~~  
~~reactability of said deposition gas.~~

38. (original) The atmosphere of claim 37 wherein said deposition gas is a film precursor deposition gas.

39. (original) The atmosphere of claim 37 wherein said deposition gas is a metal film precursor deposition gas.

Claims 40-66 (cancelled).